

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

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|--|---|---------------|---------------|
| In re United States Patent Application of: |) | Docket No.: | 020732-97.668 |
| |) | | (7493) |
| Applicants: |) | Conf. No.: | 4823 |
| Applicants: |) | | |
| Application No.: |) | Art Unit: | 1752 |
| Application No.: |) | | |
| Date Filed: |) | Examiner: | LE, Hoa Van |
| Date Filed: |) | | |
| Title: |) | Customer No.: | 24239 |
| Title: |) | | |
| COMPOSITION AND PROCESS FOR |) | | |
| POST-ETCH REMOVAL OF |) | | |
| PHOTORESIST AND/OR |) | | |
| SACRIFICIAL ANTI-REFLECTIVE |) | | |
| MATERIAL DEPOSITED ON A |) | | |
| SUBSTRATE |) | | |

**AMENDMENT RESPONDING TO FEBRUARY 24, 2009 OFFICE ACTION IN UNITED
STATES PATENT APPLICATION NO. 10/792,038**

Mail Stop Final
Commissioner for Patents
PO Box 1450
Alexandria, VA 22313-1450

Sir:

This responds to the February 24, 2009 Office Action in the above-identified application.

Please amend the claims, as set out in the following **Section I (the Claims)**.

Remarks addressing the substance of the February 24, 2009 Office Action are set out in the **Section II (Remarks)** hereof.